

**Search Notes**

Application No.

09/898,431

Examiner

Mary C Hogan

Applicant(s)

GRANIK ET AL.

Art Unit

2123

**SEARCHED**

Class	Subclass	Date	Examiner
703	13	1/13/2005	MCH
716	4,8,19	1/13/2005	MCH

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Inventor Name Search: EAST, IEEE, ACM	1/13/2005	MCH
EAST:optical proximity correction, etch, simulate, mask, reticle, layout, lithograph	1/13/2005	MCH
IEEE:optical process correction, opc, etch, mask or reticle	1/13/2005	MCH
ACM: "optical process correction" "etch effect" etch lithography layout simulation "optical proximity correction" opc	1/13/2005	MCH
Proquest: optical process correction, optical proximity correction	1/13/2005	MCH